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IEE CNF	IEE Conference Proceeding			Semiconductor Manufact 14-15 June 2000 Page(s		Workshop, 2000	
IEEE STD	IEEE Standard			Digital Object Identifier 1		•	
				AbstractPlus   Full Text:	<u>PDF(</u> 556 KB) IE	EE CNF	
			2.	Defect inspection sam Scanlan, B.; Advanced Semiconduct 23-25 Sept. 1998 Page( Digital Object Identifier	or Manufacturing ( s):103 - 108	Conference and Workst	nop, 1998. 19
				AbstractPlus   Full Text:	PDF(660 KB) IE	EEE CNF	
		<u>.</u>	3.	Development of cost e Tomlinson, W.; Nurani, I Advanced Semiconduct 10-12 Sept. 1997 Page( Digital Object Identifier 1 AbstractPlus   Full Text:	R.K.; Burns, M.; Si or Manufacturing ( s):8 - 12 0.1109/ASMC.19	hanthikumar, J.G.; Conference and Worksł 97.630696	
			4.	A methodology for det the photolithography r fabricator Butler, K.L.; Woods, R.; Advanced Semiconduct 8-10 Sept. 1999 Page(s Digital Object Identifier 1 AbstractPlus   Full Text:	or Manufacturing ( 0:113 - 116 0.1109/ASMC.19	in a multi-part numbe Conference and Worksh 99.798195	r, multi-tech
				A TOUR OCK THE   THE TEXT.	<u> (</u> 030 ND) 10	LE VIII	
	•		5.	Key considerations in McIntyre, M.; Nurani, R. Advanced Semiconduct Proceedings. IEEE/SEM 12-14 Nov. 1996 Page(s	K.; Akella, R.; or Manufacturing ( II 1996		_

Digital Object Identifier 10.1109/ASMC.1996.557977

<u>AbstractPlus</u> | Full Text: <u>PDF</u>(484 KB) IEEE CNF

<ol> <li>Defect sampling methodology: the development of an effective defect saiduring the initial start-up phase of a 0.35 /spl mu/m fabrication facility Cappel, R.; Hilton, R.; Lim, J.;</li> <li>Advanced Semiconductor Manufacturing Conference and Workshop, 1995. AS Proceedings. IEEE/SEMI 1995</li> <li>13-15 Nov. 1995 Page(s):271</li> <li>Digital Object Identifier 10.1109/ASMC.1995.484384</li> </ol>
AbstractPlus   Full Text: PDF(36 KB)   IEEE CNF
<ol> <li>Process control and base line monitoring using optical 'On the Fly' and S classification as implemented in advanced DRAM manufacturing Ralf, S.; Sina, P.; Dvori, S.; Bernhard, M.; Advanced Semiconductor Manufacturing Conference and Workshop, 2003 IEE 31 March-1 April 2003 Page(s):67 - 72</li> </ol>
AbstractPlus   Full Text: PDF(498 KB)   IEEE CNF
8. Role of in-line defect sampling methodology in yield management Nurani, R.K.; Akella, R.; Strojwas, A.J.; Wallace, R.; Semiconductor Manufacturing, 1995., IEEE/UCS/SEMI International Symposiu 17-19 Sept. 1995 Page(s):243 - 247 Digital Object Identifier 10.1109/ISSM.1995.524400  AbstractPlus   Full Text: PDF(460 KB) IEEE CNF
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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	103	702/83.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 15:45
L2	1	702/83.ccls. and (metrology with sampl\$3 with rule)	US-PGPUB	OR	ON	2005/09/01 15:46

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	103	702/83.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 09:07
L9	5	L1 and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 09:38
L10	13	purdy-matthew-\$.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 09:39
L11	17910	advanced adj micro adj devices\$.as.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 09:39
L12	17	(L10 L11) and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:36
L13	. 2231	700/96,121,108-110.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:36
L14	35	L13 and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:42

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L17	4	L13 and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer) and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) same (sample sampling) same (value weight\$3) same (active initiat\$3 trigger\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:43
L18	4785	((702/81,83,84,182-185) or (700/90,108-111)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/01 10:42
L19	7398	((702/81,83,84,182) or (700/95, 108-110,116,117,121) or (438/5,7, 8,14)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/01 10:42
L20	97	(L18 L19) and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:47
L22	49	("6392229" "4864522" "4969191" "6766214" "6821792" "6424876" "6780552" "5712707" "5757507" "5621514" "4798469" "4804924" "4857836" "5206820" "5563709" "5576948" "5739524" "5778016" "5789124" "5900624" "5940194" "6023338" "6072899" "6079256" "6100978" "6166801" "6225639" "6225639" "6225639" "6236344" "6246044" "6266581" "6396856" "6427345" "6442496" "6494766" "6524165" "6650955" "6754593" "6764380" "6833221" "6842251" "6859746" "6891626" "6897665" "6899982" "6922600" "5442166" "5731877" "6226074").pn.	US-PGPUB; USPAT	OR	ON	2005/09/01 10:46

L23	5	(L22) and (sampl\$3 with (significance magnitude substance value weight\$3)) and (active initiat\$3 trigger\$3) and sampl\$3 and process and sampling and (rule plan condition parameter) and (work\$piece (work adj piece) lot wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 10:47
L24	5	("5150289"   "5465221"   "5497331"      "5761064"   "5862054").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/01 10:50
L25	8	("6477432").URPN.	USPAT	OR	ON	2005/09/01 10:51

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	10/634013	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:36
S2	13	purdy-matthew-\$.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 18:54
S3	17866	advanced adj micro adj devices\$.as.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 18:54
S4	2	(S2 S3) and metrology and weight and trigger	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 18:57
S6	101	702/83.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 18:56
<b>S7</b>	1	S6 and metrology and weight and trigger	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 09:07
<b>S9</b>	117	metrology and weight and trigger not S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 19:05
S11	73	metrology and weight and trigger and semiconduct\$3 not S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 19:05
S12	35	metrology and weight and trigger and semiconduct\$3 and value and rule not S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/08/22 19:06
S13		metrology and weight and trigger and semiconduct\$3 and value and rule and lot not S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/22 19:09

S14	2	(("5541846") or ("6442496")).PN.	US-PGPUB; USPAT	OR	OFF	2005/08/22 19:09
S16	48	(("(6392229") or ("4864522") or ("4969191") or ("6766214") or ("6821792") or ("6424876") or ("6780552") or ("5712707") or ("5757507") or ("5621514") or ("4798469") or ("4804924") or ("4857836") or ("5206820") or ("5563709") or ("5576948") or ("5739524") or ("5789124") or ("6023338") or ("6072899") or ("6079256") or ("6100978") or ("6166801") or ("6225639") or ("6233056") or ("6236344") or ("6396856") or ("6427345") or ("6396856") or ("6494766") or ("6524165") or ("6650955") or ("6754593") or ("6897665") or ("6891626") or ("6897665") or ("689982") or ("6897665") or ("689982") or ("67531877") or ("6226074).pn.")). PN.	US-PGPUB; USPAT	OR	OFF	2005/08/25 08:16
S17	45	S16 and metrology and sampl\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 08:45
S18	6	S16 and metrology and sampl\$3 and weight	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 09:03
S21	3	"6708129".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 08:58
S22	4770	((702/81,83,84,182-185) or (700/90,108-111)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/25 08:58
S25	7369	((702/81,83,84,182) or (700/95, 108-110,116,117,121) or (438/5,7, 8,14)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/25 09:00

529	36	(S22 S25) and metrology and sampl\$3 and weight	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON.	2005/08/25 09:03
S30	22	(S22 S25) and metrology and sampl\$3 and weight and process and controller	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 09:03
S31	8	(S22 S25) and metrology and sampl\$3 and weight and process and controller and dynamic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 09:05
S33	2	(S22 S25) and (metrology with sampl\$3) and weight and process and controller and dynamic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:20
S34	2	"6477432".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:31
S35	5	("5150289"   "5465221"   "5497331"   "5761064"   "5862054").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/25 10:23
S36	8	("6477432").URPN.	USPAT	OR	ON	2005/08/25 10:26
S37	3	"6442496".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:31
S38	3	("6245581"   "6248602"   "6337217").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/25 10:32
S39	8	("6442496").URPN.	USPAT	OR	ON	2005/08/25 10:34
S40	1	"6859746".pn.	USPAT	OR	ON	2005/08/25 10:34
S41	27	("20020135781"   "20030204348"   "20040121495"   "5867276"   "5877860"   "5880838"   "5956692"   "6051348"   "6055463"   "6081334"   "6115643"   "6141107"   "6223098"   "6245584"   "6319884"   "6383888"   "6423977"   "6433878"   "6445969"   "6479200"   "6529282"   "6597447"   "6643557"   "6650955"   "6721939"   "6742168"   "6766214").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/25 10:34

S42	1	(metrology with sampl\$3 with rule) and (workpiece lot) and wafer and ((trigger active stimulus threshold) with value)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:40
S44	27	(metrology with sampl\$3) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:41
S45	27	(metrology with sampl\$3) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value) and process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:41
S47	27	(metrology with sampl\$3) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value) and process and (micro\$processor (micro adj processor) controller computer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:42
S48	27	(metrology with sampl\$3) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value) and process and (micro\$processor (micro adj processor) controller computer) and tool	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 13:43
S49	5	(metrology with sampl\$3) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value) and process and (micro\$processor (micro adj processor) controller computer) and tool and rule	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 08:19
S51	16	S49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 14:22
S52	11	(S49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn. "6687561".pn.) and (metrology with sampl\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 14:30
S53	1	(S49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn. "6687561".pn.) and (metrology with sampl\$3) and (workpiece lot) and (sampl\$3 with rule)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 14:36

S54	5	(\$49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn. "6687561".pn.) and (metrology with sampl\$3) and (workpiece lot) and rule	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2005/08/30 14:33
S55		(\$49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn. "6687561".pn.) and (metrology with sampl\$3) and (workpiece lot) and (sampl\$3 with (condition rule ruling))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 14:38
S56	5	(S49 "6871114".pn. "6477432".pn. "6442496".pn. "6859746".pn. "6650955".pn. "6687561".pn.) and (metrology with sampl\$3) and (workpiece lot) and (sampl\$3 with (plan condition rule ruling))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 16:29
S57	2	"6650955".pn. and (metrology same sampling same plan)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 08:26
S59	. 3	(metrology same sampl\$3 same plan) and (workpiece lot) and wafer and ((trigger active stimulus threshold activate actuate) with value) and process and (micro\$processor (micro adj processor) controller computer) and tool	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 08:19
S60	1166	sampling with weight\$3 with value	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 08:26
S61	5	(sampling with weight\$3 with value) and metrology	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/08/31 13:50
S62	2	"6477432".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 14:10
S63	2	"6477432".pn. and (lot same rule same sampl\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:26

S64	491	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) same sampl\$3 same (trigger\$4 threshold\$3 value) same (weight condition rule))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:37
S65	35	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$\$3 total combination) same sampl\$3 same (trigger\$4 threshold\$3 value) same (weight condition rule)) and metrology	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/08/31 15:40
S66	18	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) same sampl\$3 same (trigger\$4 threshold\$3 value) same (weight condition rule)) and metrology and defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/08/31 15:41
S67	8	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) same sampl\$3 same (trigger\$4 threshold\$3 value) same (weight condition rule)) and metrology and defect and inspection	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON ,	2005/08/31 15:41
S68	3	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$\$3 total combination) same sampl\$3 same (trigger\$\$4 threshold\$\$3 value) same (weight condition rule)) and metrology and defect and inspection and lot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON -	2005/08/31 15:47
. S70	41	(semiconduct\$3 same wafer) and process and ((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:48

S72	141	((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) same (sample sampling) same (weight condition rule) same (trigger\$4 threshold\$3 value)) and lot and wafer and semiconduct\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:51
S73	7	((cumulati\$3 collect\$3 increas\$3 grow\$3 combin\$3 summati\$3 summ\$3 total combination) with (sample sampling) with (weight condition rule) with (trigger\$4 threshold\$3 value)) and lot and wafer and semiconduct\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:51